System Model # SDW-636-CVP
Dimension：3400mm x1200mm x 190mm
POWER 1：Voltage=208V /Amp=6A
POWER 2：Voltage=110V /Amp=20A
Wafer Size=6”(150mm)

Spin unit：
Spin motor type=Brushless DC servo motor
Rotation =0 to 6000 rpm

Rotation precision：	Rotation range	linearity	Reproducibilbiy
	10~600 ：	Within +1,-5rpm	Within ± 4rpm
	600~1000 ：	Within ± 0.5%	Within ± 0.5%
	1000~6000 ：	Within ± 0.3%	Within ± 0.4%

Chemical system：
Coater resist supply= bellows pump
Coater resist filter= Millipore 0.2um
Spin unit purge=N2 purge
Coater resist nozzle= FEP capillary nozzle
Coater solvent supply= central supply(not pump)
Spin unit N2 blow/ purge system= Operates by factory line pressure.
Oven unit N2 purge system= Operates by factory line pressure.

Oven system：
Bake method= Contact bake with hot plate
Oven plate= Aluminum processed with hard alumite.
Hot plate temperature regulation=50 to 250°C set in 1°C increments
Bake/cooling time= 0 to 999 sec per 1 zone set in 1 sec increment

Contact strengthen processing：
Method= HMDS vapor rocessing in a semi-closed chamber
HMDS bubbler = Carries out N2 bubbling with the stainless steel bubbler at the bubbling tank.
HMDS vapor supply= The HMDS is forced fed to the chamber by the N2 pressure bubbling.

Program date= 9 date(D1 to D9)